



PATENT  
81839.0107

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of:

Makoto IIDA, et al.

Serial No: 10/009,910

Filed: December 12, 2001

For: SILICON WAFER, SILICON EPITAXIAL  
WAFER, ANNEAL WAFER AND METHOD  
FOR PRODUCING THEM

Art Unit: 1765

Examiner: Matthew J. Song

PETITION FOR EXTENSION OF TIME

Mail Stop AF  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

I hereby certify that this correspondence  
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John P. Scherlacher, Reg. No. 23,009

Name

Signature

Date

Dear Sir:

In accordance with 37 C.F.R. 1.136, Applicant respectfully petitions the  
Commissioner for a two-month extension of time extending to November 24, 2004,  
the period for response to the final Office Action dated June 24, 2004. Please charge  
the fee of \$430 for this extension to Deposit Account No. 50-1314. The responsive  
paper(s) are attached.

Please charge any insufficiency or credit any overpayment to Deposit Account  
No. 50-1314. A copy of this petition is enclosed.

Respectfully submitted,

HOGAN & HARTSON L.L.P.

Date: November 2, 2004

By:

John P. Scherlacher  
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